

WEST Search History

DATE: Friday, March 30, 2007

Hide?	<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>
	<i>DB=USPT; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L19	((wafer or substrate or semiconductor or object) with (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3)) same (((back plate) or (lower side) or plate or shield\$3) with (hydrophobic or polymer or resin or teflon) with (surface tension))	2
	<i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L18	((wafer or substrate or semiconductor or object) with (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3)) same (((back plate) or (lower side) or plate or shield\$3) with (hydrophobic or polymer or resin or teflon) with (surface tension))	1
<input type="checkbox"/>	L17	L16 same (liquid or solution or solvent or wet\$4 or fluid)	49
<input type="checkbox"/>	L16	(wafer or substrate or semiconductor or object) with (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3) with ((back plate) or (lower side) or plate or shield\$3) adj5 (hydrophobic or polymer or resin or teflon)	139
<input type="checkbox"/>	L15	L14 same (liquid or solution or solvent or wet\$4 or fluid)	82
<input type="checkbox"/>	L14	((wafer or substrate or semiconductor or object) with (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3)) same (((back plate) or (lower side) or plate or shield\$3) adj5 (hydrophobic or polymer or resin or teflon))	214
<input type="checkbox"/>	L13	L12 same (liquid or solution or solvent or wet\$4 or fluid)	383
<input type="checkbox"/>	L12	((wafer or substrate or semiconductor or object) with (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3)) same (((back plate) or (lower side) or plate or shield\$3) with (hydrophobic or polymer or resin or teflon))	876
<input type="checkbox"/>	L11	L10 same (liquid or solution or solvent or wet\$4 or fluid)	582
<input type="checkbox"/>	L10	(wafer or substrate or semiconductor or object) same (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3) same (((back plate) or (lower side) or plate or shield\$3) with (hydrophobic or polymer or resin or teflon))	1289
	<i>DB=USPT; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L9	L8 and l5	17
<input type="checkbox"/>	L8	(wafer or substrate or semiconductor or object) same (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3) same (((back plate) or (lower side) or plate or shield\$3) with (hydrophobic or polymer or resin or teflon))	2515
<input type="checkbox"/>	L7	(wafer or substrate or semiconductor or object) same (clean\$3 or treat\$3 or rins\$3 or wash\$3 or etch\$3) same (((back plate) or (lower side) or plate or shield\$3 or back) with (hydrophobic or polymer or resin or teflon))	3055
	<i>DB=USPT,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>		
<input type="checkbox"/>	L6	L5 and l2	10
<input type="checkbox"/>	L5	134/137,139,149,154,182,153,201,902;156/345.23,345.3.ccls.	4285
	<i>DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>		

- ☐ L4 L3 same (liquid or solution or solvent or wet\$4 or fluid) 521
(wafer or substrate or semiconductor or object) same (clean\$3 or treat\$3 or rins\$3
- ☐ L3 or wash\$3 or etch\$3)same (((back plate) or (lower side) or plate shield\$3 or 1823
back) with (hydrophobic or polymer or resin or silicon or teflon))
DB=USPT; PLUR=YES; OP=ADJ
- ☐ L2 L1 same (liquid or solution or solvent or wet\$4 or fluid) 1165
(wafer or substrate or semiconductor) same (clean\$3 or treat\$3 or rins\$3 or
- ☐ L1 wash\$3 or etch\$3)same (((back plate) or (lower side) or plate shield\$3 or back) 5693
with (hydrophobic or polymer or resin or silicon or teflon))

END OF SEARCH HISTORY